

Supporting Information

Tuning Nonlinear Optical Absorption Properties of WS₂ Nanosheets

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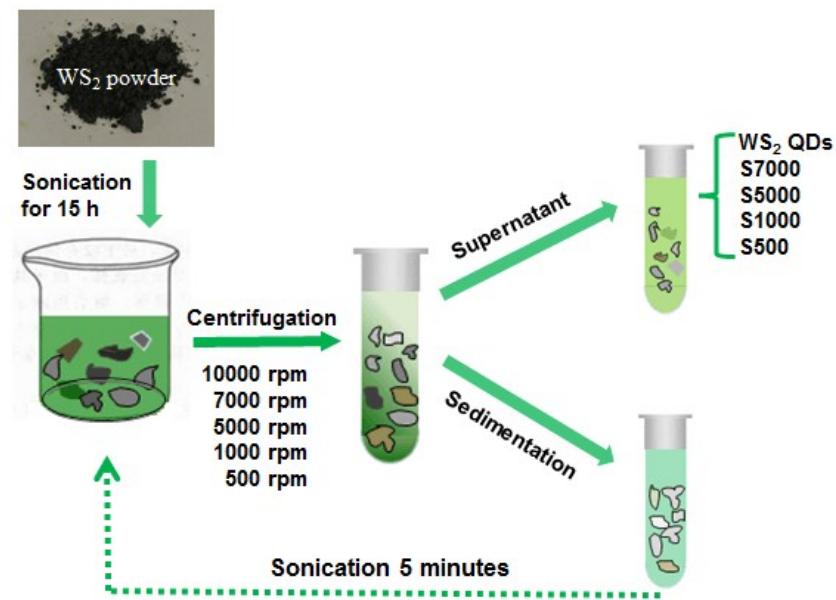


Fig. S1. Experimental procedures for fabricating WS₂ quantum dots and nanosheets with different size and thickness distribution.



Fig. S2. Digital photographs of prepared WS₂/PMMA and WS₂QD/PMMA composites. They are S500, S1000, S5000, S7000 and WS₂QDs from the left to right, respectively

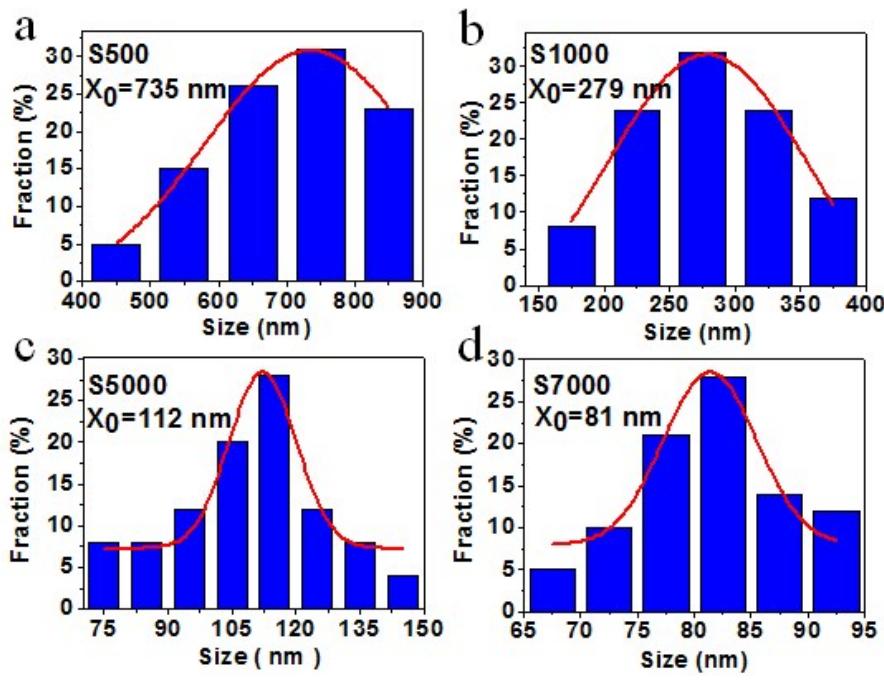


Fig. S3. Size distribution of WS_2 sheets exfoliated in NMP and subsequently separated under different centrifugation rates of a-500, b-1000, c-5000, and d-7000 rpm, respectively.

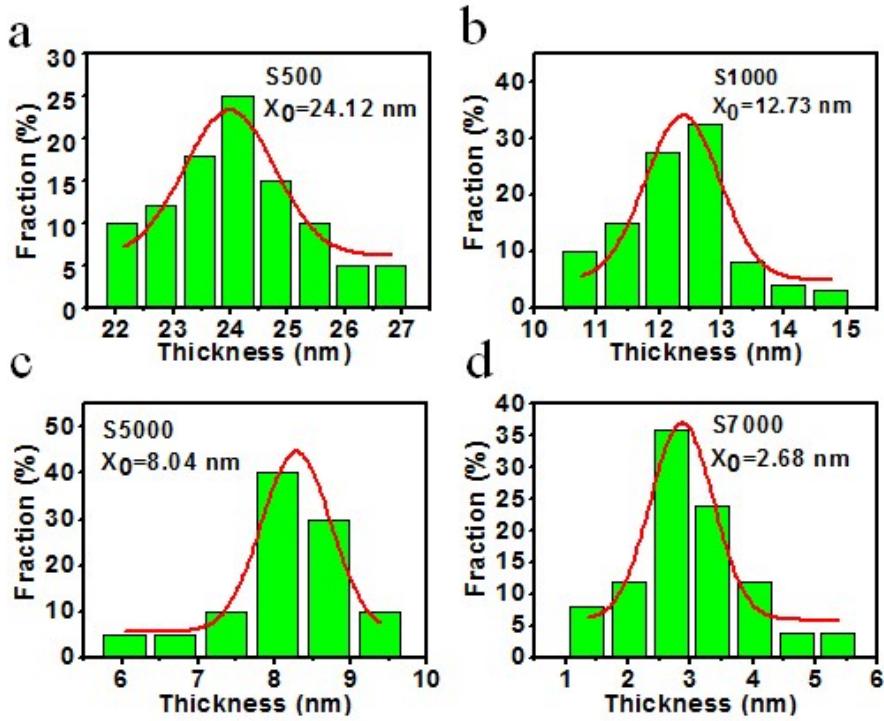


Fig. S4. Thickness distribution of WS_2 sheets exfoliated in NMP and subsequently separated under different centrifugation rates of a-500, b-1000, c-5000, and d-7000 rpm, respectively. The interlayer space of WS_2 is 0.62 nm.

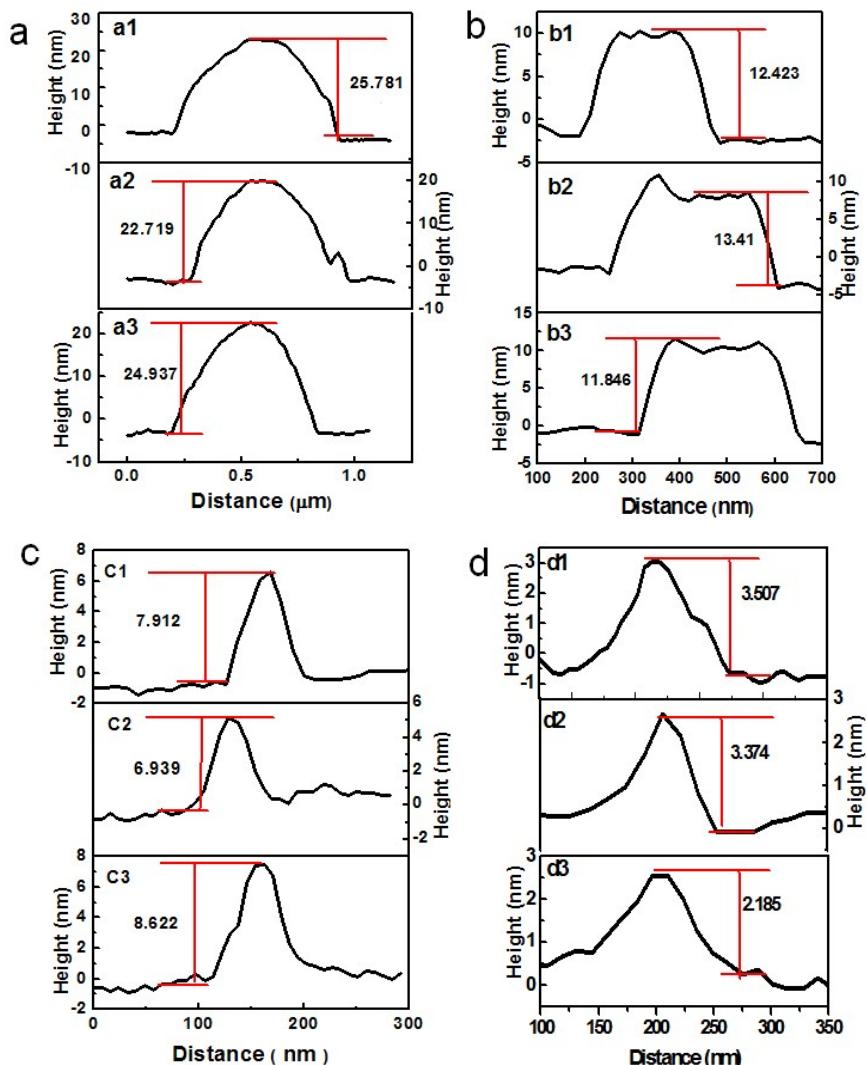


Fig. S5. Randomly selected section height profiles of WS₂ sheets exfoliated in NMP and subsequently separated under different centrifugation rates of a-500, b-1000, c-5000, and d-7000 rpm, respectively. The interlayer space of WS₂ is 0.62 nm.

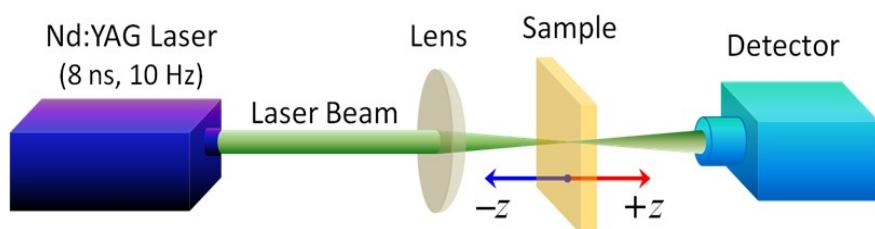


Fig. S6. Experimental setup of Z-scan technique.

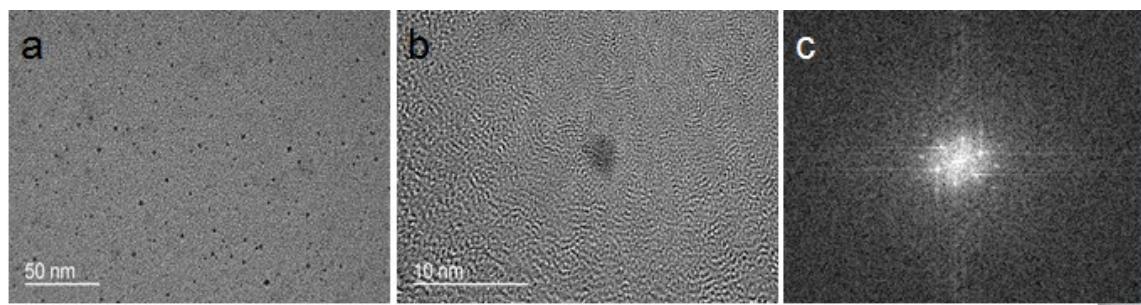


Fig. S7. a) TEM image of the WS₂QDs assembled on Cu grid coated with ultrathin amorphous carbon film; b) HRTEM image of a typical single WS₂QD, and corresponding selected area FFT image c).

Table S1. The nonlinear optical property onset thresholds (F_{ON}) and optical limiting thresholds (F_{OL}) of different materials for the nanosecond laser operating at 532 and 1064 nm, respectively.

Materials	532 nm			1064 nm		
	T _L (%)	F _{ON} (J/cm ²)	F _{OL} (J/cm ²)	T _L (%)	F _{ON} (J/cm ²)	F _{OL} (J/cm ²)
Pd NW ¹	80	0.09	0.90	80	0.30	8.00
CdS NPs ²	70	0.30	2.55	70	1.00	16.40
Au NP ³	70	0.07	0.60	77	0.60	7.50
MWCNTs ²	70	0.04	0.68	70	0.13	9.69
CNTs-PTh-CdS ²	70	0.03	0.47	70	0.09	6.66
GO ⁴	70	0.19	1.19	75	1.36	10.32
GO NRs ⁵	70	0.10	1.00	70	0.20	4.00
PNP ⁺ GO ⁻ ⁶	63	0.21	1.55	74	2.00	8.10
PEG-OPE-rGO ⁴	70	0.07	0.31	75	0.54	3.50
Graphene NSs ⁵	70	0.10	0.50	70	0.20	6.30
Graphene NRs ⁵	70	0.10	0.70	70	0.20	3.40
Graphene ⁷	73	0.01	0.08	85	0.01	0.1
MoS ₂ /PMMA ⁸	44	0.01	0.40	53	0.04	1.30
S7000*	44	0.011	0.245	65	0.036	0.48
WS ₂ QD/PMMA*	48	0.010	0.062	63	0.030	0.10

*This work

Table S2. The absorption coefficient α ($\text{L g}^{-1} \text{cm}^{-1}$) of different samples at 532 and 1064 nm, respectively.

Samples	S500	S1000	S5000	S7000
α ($\text{L g}^{-1} \text{cm}^{-1}$) @ 532 nm	13.98	21.84	27.92	32.21
α ($\text{L g}^{-1} \text{cm}^{-1}$) @1064 nm	8.26	10.78	10.85	10.95

References:

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